# **Device Requirements and Challenges of Mixed-Signal Neuromorphic Hardware**

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# Outline

- Introduction to models, applications & digital hardware
- Neurocomputing with memory devices
- Device requirements & challenges
- Examples of recent mixed-signal accelerator prototypes
- Concluding remarks



# Part I. Neural Network Models, Applications, and Digital Hardware



#### **Neural Network Zoo**



- Networks differ mostly by neuron connectivity & neuron functionality (more complex towards the right)

## **The Most Important Operation in Neural Networks**



Vector-by-matrix multiplication is the most common operation



### **Practically Useful Neural Network Models**



#### **Largest Neural Network Models**



- >8B weights / >10<sup>19</sup> FLOPs training cost in the state-of-the-art attention (transformer) networks

- Larger network → better quality





	Importance (world total in 2020, Source: NVIDIA)	Key differences in HW specs	Where deployed	Primary HW metric
Training	~55 ExaFLOP/s	Medium-to-high (8÷32 bit) computing precision	cloud	Throughput per chip area
Inference	~450 ExalOP/s FLOP = floating point op IOP = integer op Exa = 10 <sup>18</sup>	Low-to-medium (4÷8 bit) computing precision Persistent (nonvolatile) weights	cloud edge	Throughput per chip area Energy efficiency
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## **State-of-The-Art Deep Learning Hardware**

commercial digital systems for high performance and mobile applications 100s W, \$\$\$\$ few W, \$\$



NVIDIA's Turing (12 nm)

> Google Edge TPU

**NVIDIA's Jetson** 

Google's Tensor Processing Unit





Intel's Movidius



## State-of-The-Art Deep Learning Hardware

#### custom experimental digital systems

**Startups:** Cerebras, Habana, Wave Computing, Graphcore, Groq ...

#### **Cerebras (largest chip ever built)**



46,225 mm<sup>2</sup> 1.2T trans @ 16 nm 18 GB on-chip memory



Min/max energy efficiency [TOps/J] 0.26–10 (~2.5 @ 4-bit) 11.6(4 bit) / 3.08(16 bit) ~ 9.09 (8 bit)

\* AlexNet convolutional layers only

- Saturating performance/energy efficiency, limited on-chip memory, expensive (\$300M design cost in 7 nm)
- Biology is many orders of magnitude more energy efficient



#### **Problems with Digital Accelerators**





# Part II. Neurocomputing with Memory Devices

## **Implementing Basic Neuromorphic Operation**

**Dot-Product Computation ...** 





## **Implementing Basic Neuromorphic Operation**

#### **Dot-Product Computation ...**

... by Analog Circuit



- Utilize fundamentally accurate Ohm's and Kirchhoff's laws
- In-memory computing (no need to move around synaptic weights)



## **Implementing Basic Neuromorphic Operation**



... by Analog Circuit



- No <u>dense</u> adjustable-conductance nonvolatile devices until recently



## **Earlier Work on Analog Neurocomputing**

#### Widrow's "Memistor"

AdaLiNe concept and its hardware implementation





B. Widrow and M.E. Hoff, Jr., *IRE WESCON Convention Record*, 4:96 1960

- Automated 4×4 b/w image classification in follow-up early 1970s work
- Coincided with the rise of digital processors (Intel 4004)

#### "Synaptic Transistor"

(from the late 1980s: C. Mead, C. Diorio, J. Hasler,...)

"Extended drain" NMOS structure





#### Hasler's recent FPAA chip



S. George et al. IEEE Trans. VLSI, 2016

>1000 *F*<sup>2</sup> per synaptic weight!

**PRO**: allow using common CMOS foundries **CON**: large cells  $\rightarrow$  low speed  $\rightarrow$  low energy efficiency



#### **New Life for Old Concept**

#### **Metal-Oxide Memristors**

#### **Analog VMM Circuit**



Applying  $|V| \le V_R$  does not disturb the memory state for nonvolatile memristors



#### **New Life for Old Concept**

#### **Metal-Oxide Memristors**

#### **Analog VMM Circuit**



Tunable conductance, nonvolatile, extremely compact footprint when using passive memristors



## **Different Options for Analog / Mixed-Signal VMMs**

(classification based on how P-bit inputs are encoded)

Instant



- Inputs are encoded in voltage amplitudes
- Dot-product is proportional to the output current



- Digital inputs are presented bit-by-bit

Encoding in biology is closer to the fixed-amplitude / variable duration scheme

- Dot product is accumulated in *P* steps by successive integration and re-scaling
- Or accumule in digital domain (HP's ISAAC)



**Exponential** 

- Digital inputs are encoded in duration of fixed-amplitude pulses
- Dot product is proportional to the output pulse duration

*M. Bavandpour et al, IEEE S3S, 2019 M. Bavandpour, S. Sahay et al, IEEE TVLSI, 2019* 



#### **Approximate Content Addressable Memory (CAM)**

also known as "hyperdimensional" memory



- CAM's essential operation is Hamming distance calculation
- Hamming distance between two vectors = dot-product of two vectors

Hyperdimensional computing is VMM with binary weights/inputs followed by winner-take-all circuit



#### **Memory Array Options**







need very uniform devices

less dense due to bulky transistor

relaxed d2d requirement





#### **Tunable Non-Volatile Memory Device Options**

# **General Philosophy for System Level Demo**

- Focus on ex-situ-trained neuromorphic inference
  - the simplest, yet very practical
- Has to be flexible enough
  - to run all recent practical NN models for image and language processing, e.g. those Google reported as workloads on their data centers
- Mixed-signal design
  - Most of the NN models rely on the weight reuse, which implies producing and storing some intermediate temporary data in the network. Temporary data are better to store in digital domain
  - Digital for more exotic (e.g. vector-by-vector outer product computations, different activation functions)
  - Analog circuits to implement dense VMMs, which dominate inference in all models



## **UC Santa Barbara's Inference Accelerator**

aCortex architecture (one tile)

Neuron ADC

Auxiliary

**Buffer** 

DAC FG array Sensing



#### **Details:**

- Custom (<u>energy-optimized</u>) mixedsignal architecture, with estimates shown for NOR flash (projected from 100k-weights experimental chip)
- Analog neuron input bus
- Digital interfaces (DACs/ADCs)

 System-level estimates for 55 nm NOR flash 4-bit and comparison with digital counterpart at the same compute precision / process node

	INC-V1	ResNet	GNMT						
Network specifications									
# parameters	7.2e06	1.1e07	1.3e08	DI					
# operations	5.2e09	2.0e10	2.6e09						
Area breakdown (%)									
MM	18.1	4.53	2.2						
Sensing	15.5	23.3	25.1						
FG arrays	24.2	36.5	39.3	2					
P/E	26.3	14.7	11.3						
Others	16	23	22.1						
Energy br	eakdow	n (%)							
MM	38.8	23.9	8.3						
Sensing	16.2	11.4	23.8						
FG arrays	3.03	2.13	4.45						
Buses	31.6	41.3	12.4	2					
Leakage (buses)	4.4	17.4	46.7	4					
Others	6.9	4	4.4						
Performance summary									
Area (mm <sup>2</sup> )	35.4	142	293						
Power (mW)	14.9	19.8	16.1						
Latency (ms)	3.1	8.75	0.59						
EE (TOp/J)	114	120	283	3					
Throughput (TOp/s)	1.69	2.37	4.54						

-	System-level efficiency
	for EE-optimized
	designs is mainly
	limited by memory
	density

Chip area Latency

(ms)

749

0.59

 $(mm^2)$ 

257

293

**Digital CMOS** 

Analog FG

EE

(TOp/J)

0.14

283

 Small networks (e.g. with <~10<sup>4</sup> Op / pixel in 55 nm) will be dominated by I/O

M. Bavandpour et al, IEDM, 2018



#### **Conductance Tunability at Rescue from Process Variations**



Memory state tunability  $\rightarrow$  low overhead for dealing with process variations



## **Tradeoff between Energy-Efficiency and Throughput**

Energy-efficient design (for edge) less periphery / more compact



High-throughput design (for cloud) more VMM computations in parallel





## **Tradeoff between Energy-Efficiency and Throughput**



Natural tradeoff between energy efficiency and throughput (at device, circuit, architecture levels)



## **Tradeoff between Energy-Efficiency and Throughput**



Mixed-signal for low-to-medium precision & EE optimal, digital for higher precision & throughput-optimal



#### **Proper Way to Compare Performance Metrics**

#### Tradeoff between energy-efficiency and functional performance (image classification accuracy)



System-level energy cost (e.g. energy/inference) Source: J. Deguchi et al, IEDM'19 Report chip or system level metrics, e.g.

- Frames per seconds per area at certain accuracy
- Energy per inference at certain accuracy

Oblivious to type of network / computing precision / type of hardware

TOP/s/cm<sup>2</sup> or TOP/J as proxy could be very misleading

Useful applications for lower accuracy?



## **Part II: Key Takeaways**

- Memristors are enabling element for VMMs
- >100x better chip-level energy-efficiency for inference accelerators due to
  - compact footprint & tunability of passively integrated memristors
  - "in-memory" computing in analog VMM circuits
- Digital conversion circuits, needed to take advantage of weight reuse, reduce processing throughput



# Part III. Device Requirements and Challenges

## **CMOS Compatibility**

Hybrid monolithic 3D hybrid circuits using passively integrated devices as an ultimate goal



passively back-end integrated **memristor** crossbar (synapses)

**CMOS stack** (neurons and other peripheral functions)

Device Requirement: Compatible with CMOS backend memristor integration process and memristor operation



#### **Key Operations on Memristor Crossbar Circuits**





#### **Crossbar Compatible Forming**



Large, potentially destructive currents through already formed crosspoint devices when  $V_{\text{forming}} >> V_{\text{w}}$ 

<u>Device Requirement</u>: Forming process compatible with passive crossbar circuits (relaxed for 1T1R circuits)



### **Endurance, Switching Speed/Energy**



For ex-situ trained inference accelerators weights are programmed (tuned) infrequently

→ Acceptable to use slow / power hungry write-verify algorithm, which adapts to the variations in the device I-Vs



#### **Endurance, Switching Speed/Energy**



Write speed / energy, switching endurance, switching dynamics are not important for inference Less severe requirements for device variations for inference



## **Static I-V linearity**



- Linear I-V is needed for precise multiplication, e.g.  $I(V_R) / (2I(V_R/2)) > 0.95$  for 4-bit precision
- I-Vs are typically very linear at small (non-disturbing) voltages



## Major Challenge #1: Poor Yield of Memory Devices

• Impact of bad devices: study of finding the largest fraction of bad devices for 95% successful mapping



- Simplified model assuming stuck-on-off bad devices (failed to form) or out-of-spec (with poor retention, high noise)
- Some overhead for permuting block's input/output
- Higher tolerance with chip-in-the-loop / defect-aware ex-situ training (*F. Merrikh Bayat et al, ICCAD'19*) but less viable commercially



## Major Challenge #2: Switching Threshold Variations

Switching voltage threshold variations



 Switching threshold = voltage at which current changes by > 10% when applying voltage ramp Half-select disturbance



- Disturbance of half-selected devices when tuning devices with the largest voltage threshold
- at least c.v. < 0.3 for "V/2–biasing" scheme, with σ margins, and naïve algorithm to avoid disturbance
- No such problem for 1T1R memories (at the cost of 100-1000x larger cell so far)



D. Strukov, Nature Materials, 2019

## **Weight Tuning Requirements for Inference Applications**



#### Impact of weight precision on ImageNet classification

Further improvements possible, e.g. perform some critical operations in digital domain

No loss in performance for ~  $3 \% \div 0.2 \%$  tuning precision in the dynamic range





## Major Challenge #3: High Cell Current

#### Why it is a problem?

- larger operating (read) currents → smaller input/output array impedance
  → larger DAC/sensing overhead
- large write currents limits the size of the passive crossbar arrays due to IR drop or swells access transistor in active arrays

#### Pros of some active cells:



## **Part III: Key Takeaways**

- For the simplest, yet most practical neuromorphic inference applications, the most important metrics:
  - CMOS and crossbar compatibility
  - density, especially for energy-efficiency optimal designs
  - multi-level analog memory ( $4 \div 8$  bits or  $32 \div 256$  states)
  - high retention (~ months)
- Key challenges are
  - poor device yield and I-V uniformity (need < 1% bad devices, sigma  $V_{sw} << V_{sw} / 2$ )
  - high switching / operating currents (need 100s pAs to 10s nAs for operation)
- Less important / desired specs ease to achieve: dynamic / static I-V linearity, write speed/energy, endurance, noise (RTN could be too high for some devices), ON/OFF ratio
- Much more demanding device uniformity requirements for on-line/in-situ learning, e.g. SNN with STDP learning, though relaxed retention requirements for training accelerators



< 3% tuning

accuracy in the

dynamic range

Part IV. Examples of Recent Mixed-Signal Neuromorphic Hardware Prototypes

#### **UMich's Chip with Backend-Integrated Metal-Oxide Memristors**



- The first fully-integrated CMOS / 0T1R memristor chip of its kind
- Poor ~ min-scale retention, only small fraction (16×14) of memristors used at demo, very limited statistics, poor 600 μm<sup>2</sup> per cell density, small ~2.5 ON/OFF range



#### **UCSB's Metal-Oxide Memristor Chip**



#### MNIST classification demo



High precision conductance tuning



- Dark dots: ~1% devices that cannot be switched -Color encoding: 256 levels from white (10  $\mu$ S) to black (100  $\mu$ S) @ 0.2V -< 5% / < 3% absolute / relative tuning error using automated algorithm, with reserves for improvement

H. Kim *et al.* 2019 (unpublished)

<u>Other work on classifier demos:</u> M. Prezioso *Nature* 15, *IEDM* 15, F. Merrikh Bayat *Nat.Comm*.18 <u>Recent work on 3D circuits</u>: I. Kataeva *ISCAS* 19, B. Chakrabarti *Sci. Rep* 17, G. Adam *TED* 17

## Highest complexity analog-grade passive xbar demo Details:

- Al<sub>2</sub>O<sub>3</sub>/TiO<sub>2-x</sub> active bilayer by reactive sputtering
- ~250 nm wide lines, passive (0T1R) integration, 0.25 µm<sup>2</sup> per memory cell
- CMP/dry etching and TiN/AI electrodes for higher conductance
- Uniform I-Vs (~1% unswitchable devices, ~26% variation in threshold)

#### Important future steps:

- 3D monolithic integration with CMOS (ongoing E2CDA work)
- Lowering device resistance (by feature size scaling)

### HPL / UMass 1T1R Metal-Oxide Memristor Chip





- The first fully integrated CMOS / 1T1R HfO<sub>2</sub> memristor chip of its kind
- Very high >99% yield, linear I-V, excellent analog properties
- Used in many impressive demos (inference, training, reinforcement learning, unsupervised learning)
- Extremely bulky ~2,500 µm<sup>2</sup> cells, High (~ 1 mA for ON state) currents



## **Tsinghua U's 1T1R Memristor Chip for Neurocomputing**



- Largest scale demo of its kind
- Board-level integrated CMOS neural nework circuitry with 8 1T1R memristor chipw
- Each chip is 128x16 1T1R array of TiN/TaO<sub>x</sub>/HfO<sub>x</sub>/TiN devices
- Used to demonstrate convolutional neural network
- Extermely bulky ~ 200 µm<sup>2</sup> cell



## **Neuromorphic Inference with 2D NOR flash**

#### High-level architecture

#### NOR eFlash chip



#### Summary:

- 28x28 B/W input, 10-class output, >100,000 NOR flash synapses, 64 hidden layer CMOS neurons, 180-nm process with eFlash
- 94.65% experimental fidelity (96.5% theoretical)
- < 1-µs latency, < 20 nJ energy per pattern (reserves for improvement for both with better neuron design)
- Much better in speed and energy efficiency over digital circuits at comparable MNIST fidelity (10<sup>6</sup> better energy-delay than IBM TrueNorth)
- Reproducible, temperature insensitive, no change in performance after 7 months
- More recent work using 55-nm ESF3 NOR-flash technology (CICC'17, IEDM'18'19), scalable to 28 nm



**Measured results** 

# **Solving Optimization Problems with Hopfield Network**

#### Stochastic dot-product circuit:

add intrinsic/extrinsic noise from memory array to dot-product current and feed it to comparator



M.R. Mahmoodi et al. Nature Communications, 2019

#### Basic idea of the demo:



Hopfield Network (HN)



#### Experimental results for weighted graph partitioning



More results using 64×64 passive memristor xbar

- weighted max-clique
- weighted vertex cover
- independent set
- weighted graph partitioning
   M.R. Mahmoodi et al. IEDM'19
- Sigmoid slope (i.e. SNR or compute temperature T) controlled dynamically by the applied voltage  $V_{ON}$
- Estimated >10,000x improvement for energy-delay metric over competitive approaches



## **3D NAND Inference Accelerator for Large-Scale Models**







	TPU	3D NAND
		(64 layers)
Technology node (nm)	28	55
Precision (bit)	8	4
Area (mm²)	330	18
Energy efficiency (TOp/J)	0.43	70
Throughput (TOp/s)	92	11

#### Mapping common neural models



- Experimental results, excluding the off-chip weight transfer overhead. Google's Tensor Processing Unit (TPU) is optimized for throughput
- #Results of computer simulations of 3D aCortex architectures, with all weights stored on chip, optimized for energy efficiency



## **Summary of Recent Memristor Prototypes**

Tech.	Switching Material	Refs.	Xbar Size	Yield (%)	Functional Demo	$\begin{array}{c} \text{Cell} \\ \text{Size} \\ (\mu m^2) \end{array}$	Average Forming <sup>10</sup> Current (μA) /Voltage (V)	Retention¹ (@°C)	Endurance 11 (cycles)	Tunning Precision	Set Switching Statistics (μ , σ)	G <sub>max</sub> /G <sub>min</sub> (μS/μS)	Comment on the fabrication process
0T1R	Ta <sub>2</sub> 0 <sub>5-x</sub>	[49]	18×2	100	18×2	-	250 / ~1.1	-	-	4	-	1500/850	lift-off /Pd electrodes
		[38]	16×3	78	4×3	-	1000 / ~2	-	>100 k	-	1.25 , 0.1	1800/1300	lift-off /Au and Pd electrodes
	wo <sub>x</sub>	[47]	8×8 <sup>8</sup>	-	-	0.01	-	-	-	~ 50 %*	3.5, -	4/0.1	lift-off/ /Ag electrodes
		[41]	11×3	-	11×3	-	1000 / ~1.8	-	-	-	0.85, 0.05		lift-off /Pd electrodes
		[29,39,42]	32×32	-	25×20, 5×10, 4×4	~9	>170 / NA	-	-	~ 35 %²	1.7, -	3/115	lift-off /Au and Pd electrodes
		[30]	108×54*	-	16×14, 4×4	~6005	-	< 1 min	-	-	-	2.4/1	lift-off /Au and Pd electrodes
	SiGe	[48]	14×1	-	1×1	10014	- / > 4 V	> 48 h @85°	>1 M	-	4, 0.15	40/0.16	High temperature epitaxial growth
	Ti0 <sub>2-x</sub>	[20]	10×2	100	10×2	1	100 / 6	-	-	~2 %	1, 0.1	500/50	Wired XBAR/ lift-off/Au electrodes
		[5,43]	12×12	100	12×12	0.16	200 / 1.9	>10 years @30	>200 k	< 3%	0.9, 0.1	200/6	lift-off
		[12,15]	20×20	100	20×20	0.25	220 /1.5	>20 h @120	>1 M	< 2.5%	1.0, 0.18	200/6	lift-off
		[19,44]	2×10×10	100	2×10×10	0.49/2	100 / 2.5 <sup>3</sup>	>25 h @100	>1 M	< 1%	1.1, 0.15	100/0.1	Ar IBE
		[28,17]	64×64	~99	64×64	0.25	100 / 3.2	>20 h @100 >10 years @RT	>1 M	< 5%	1.2, 0.13	200/6	Fully CMOS-compatible using etch-down planar process
1T1R	HfO <sub>2</sub>	[13,36,37,46]	128×64	>9913	128×64	~250012	-	>10 years @RT		<3.1 %⁴	2 , -	900/100	lift-off
		[35]	128×8	-	960	-	>150 / >3 V	-	-	< 35 %	-	40/5	lift-off
		[40]	1K	_	448	~25	4	~1 m @30	-	~ 20 %	3.5 , -	0.01/100	-

based on filamentary (nonvolatile) memristors

<sup>1</sup> The retention data is the *minimum* reported number and does *not* necessarily determine the time-to-failure. <sup>2</sup> Based on Fig. S3 in the supplementary information of the [29] and it is not clear if the data are obtained after tunning of all cells or recorded after programming each cell. <sup>3</sup>For the top stack, average forming voltage/current for the bottom layer is 2 V/50  $\mu$ A. <sup>4</sup> Based on Fig. S3 in supplementary information of the [46]. <sup>6</sup> Based on the cross-sectional SEM image in Figure S10. It is 256.8  $\mu$ m<sup>2</sup> based on the data in supplementary note 10. <sup>6</sup> 126 subarrays of 6×8 is used to build an array of 108×54. <sup>7</sup> Based on Fig. 4d in [47] and conductances are measured after programming each subarray, not the whole crossbar. <sup>8</sup> A 40×40 array is developed by combining 25 subarrays of 8×8. <sup>9</sup> Data for the low-resistance state with sensible gradual retention loss at high resistance levels. <sup>10</sup> Maximum set voltage is used if forming statistics are not reported. <sup>11</sup> Data might not be comparable among different works since the test conditions have been different. <sup>12</sup> Based on the SEM figures provided in Fig. 1c of both [46] and [16]. <sup>13</sup> Based on Fig.1c in [36]. <sup>14</sup> Denser single devices are reported too, but most experimental results are for 5µm × 5µm devices. <sup>15</sup> This represents the average range of conductance values observed in the crossbar. There is a significant variation between different devices.



# Part V. Concluding Remarks

# Drawing Inspiration from Human Brain for Future Neuromorphic Hardware Systems



- Is the brain structure a result of a fortunate fluke? Or it represents the best solution among different possibilities?
- Are all principles behind brain operation useful for algorithm / HW design?



# Drawing Inspiration from Human Brain for Future Neuromorphic Hardware Systems



- Human brain is
  - not superfast
  - efficient only in tasks that help to survive (e.g., cannot do number crunching)
  - outperformed by latest algorithms in speech and image (by ~4%) recognition on well defined benchmarks



# Drawing Inspiration from the Human Brain for Future Neuromorphic Hardware Systems



- Signal propagation in neuronal axons compared to integrated circuits is
  - much slower (<100 m/s cf. ~10<sup>7</sup> m/s)
  - much less energy efficient (> 1µJ cf. <50 fJ per bit per mm)</li>
- → Spike encoding is the necessity rather than useful feature?
- Brain has huge variability (because it is the most energy-efficient way to reproduce?) which is tolerated by massive space/time redundancy with unique and slow "chip-in-the-loop retraining"
- → Sparse encoding is the necessity rather than useful feature?



# Drawing Inspiration from Human Brain for Future Neuromorphic Hardware Systems



- Is the brain structure a result of a fortunate fluke? Or it represents the best solution among different possibilities? (looks like a fluke)
- Are all principles behind brain operation useful for algorithm / HW design? (definitively no)
- Not all tricks the brain uses for computing are useful
- However, we are still missing the holy grail human-intelligence algorithm



## **Artificial Intelligence / Machine Learning Hardware**



#### need efficient implementation of vector-by-matrix operation for all



# Summary (I)

- Major memristor challenges:
  - poor yield
  - poor device uniformity
  - high cell currents
- Much more severe uniformity requirements and additional device challenges (endurance, write energy) for training accelerators and on-line/in-situ learning, e.g. SNN with STDP learning





# Summary (II)

- Neuromorphic inference with ex-situ training as natural entry-level application of mixed-signal neural networks
  - the simplest in terms of device requirements, yet very practical
  - at least 100x better in energy-delay over purely digital system according to the experimental results for small-scale system, and system-level projections to bigger systems
- Most promising memory technologies
  - Long term: passive 3D memristors, 3D NAND
  - Short term: embedded NOR flash, 1T1R memristors
- More advanced networks:
  - Straightforward extension to inference accelerators for more advanced approaches (stochastic neural networks, neurooptimization, spiking neural networks)
- Need biologically plausible neuromorphic hardware for brain simulations
- Novel applications driven by analog circuits?



# When Will AI Take Over Humans?

(survey of 352 expert researchers published at NIPS'15 and ICML'15)



- 50% chance of automating all human jobs (better or more cheaply with AI) in 120 years
- Most optimistic AI progress predictions in <u>Asia</u>, least optimistic in North America

Al won't replace but rather empower human kinds! (hopefully ;)



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